

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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| Applicant | : | Hada et al. |
| Appl. No. | : | 10/557,694 |
| Filed | : | November 22, 2005 |
| For | : | RESIN FOR PHOTORESIST COMPOSITION, PHOTORESIST COMPOSITION AND METHOD FOR FORMING RESIST PATTERN |
| Examiner | : | Kelly, C. |
| Group Art Unit | : | 1752 |

PRELIMINARY AMENDMENT

Mail Stop Amendment

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination on the merits, please amend the above-captioned U.S. National Phase Application as follows:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks/Arguments begin on page 7 of this paper.